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(71) Applicant *(for all designated States except US)*: HONEYWELL INTERNATIONAL INC. [US/US]; PO Box 2245, 101 Columbia Road, Morristown, NJ 07960 (US).

(72) Inventors; and

(75) Inventors/Applicants *(for US only)*: HACKER, Nigel [US/US]; HONEYWELL INTERNATIONAL INC., PO Box 2245, 101 Columbia Road, Morristown, NJ 07960 (US). LEFFERT, Scott [US/US]; HONEYWELL INTERNATIONAL INC., PO Box 2245, 101 Columbia Road, Morristown, NJ 07960 (US). FIGGE, Lisa [US/US]; HONEYWELL INTERNATIONAL INC., PO Box 2245, 101 Columbia Road, Morristown, NJ 07960 (US). SPEAR, Richard [US/US]; HONEYWELL INTERNATIONAL INC., PO Box 2245, 101 Columbia Road, Morristown, NJ 07962 (US). BEDWELL, William [US/US]; HONEYWELL INTERNATIONAL INC., PO Box 2245, 101 Columbia Road, Morristown, NJ 07960 (US). RAMOS, Teresa [US/US]; HONEYWELL INTERNATIONAL INC., PO Box 2245, 101 Columbia Road, Morristown, NJ 07960 (US).

(74) Agents: FISH, Robert et al.; RUTAN & TUCKER, LLP, 611 Anton Blvd., 14th Floor, Costa Mesa, CA 92626 (US).

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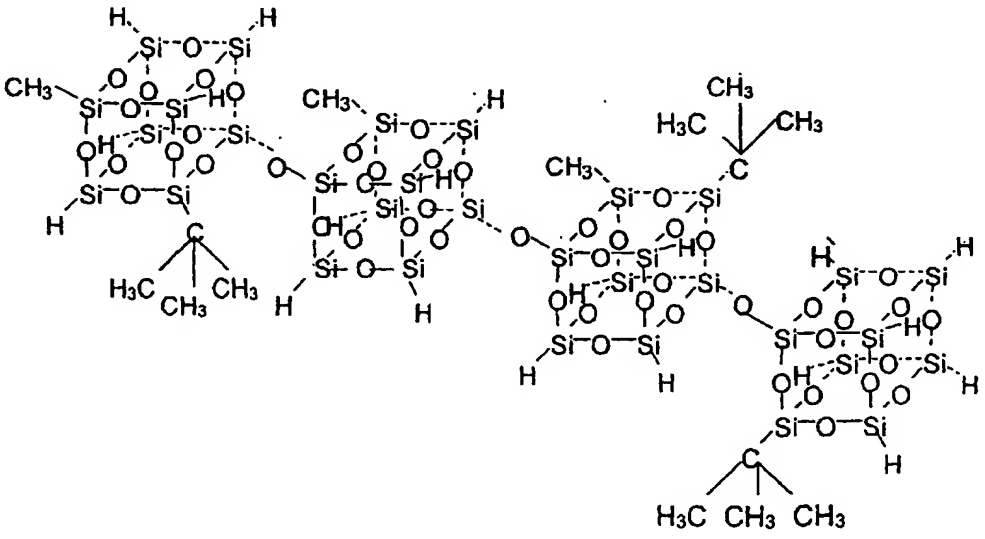
(54) Title: NANOPOROUS MATERIALS AND METHODS OF FORMATION THEREOF



(57) Abstract: Low dielectric materials are described herein that comprise a plurality of pores or nanopores in addition to the ultrananopores.It is further contemplated that the low dielectric materials described herein will have a dielectric constant of less than about 3. The dielectric materials are fromed from polymer compositions, wherein the polymer compositions comprise a plurality of monomersand wherein at least one monomer comprises a radical precursor bonded to a structural precursor. Further, methods of forming dielectric materials from polymer compositions are presented. The figure shows the chemical structure for a methyl/t-butyl Low organic Content/Low Organic Siloxane Polymer.

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